Record Nr. UNINA9910786284603321 Diffusion and diffusional phase transformation in alloys: selected, **Titolo** peer-reviewed papers fom the 4th International Workshop "Diffusion and Diffusional Phase Transformations in Alloys", DIFTRANS-2007: 16-21 July 2007, Sofoyivka (Uman'), Cherkasy region, Ukraine / / edited by D. Beke [and three others] Pubbl/distr/stampa Stafa-Zurich, Switzerland:,: Trans Tech Publications,, [2008] ©2008 **ISBN** 3-03813-204-7 Descrizione fisica 1 online resource (228 p.) Diffusion and defect forum, , 1012-0386;; v. 277 Collana Altri autori (Persone) BekeD. L (Dezso L.) Disciplina 669/.9 Soggetti Alloys Diffusion Phase transformations (Statistical physics) Lingua di pubblicazione Inglese **Formato** Materiale a stampa Livello bibliografico Monografia Note generali Description based upon print version of record. Includes bibliographical references and index. Nota di bibliografia Nota di contenuto Diffusion and Diffusional Phase Transformations in Alloys; Committees, Organizers: Preface: Table of Contents: Section 1 - Diffusion and Reactions; Silicide Formation Reactions in a-Si/Co Multilayered Samples; Lateral Diffusion Spreading of Two Competitive Intermetallic Phases over Free Surface; Theoretical Analysis and Atomistic Modelling of Diffusion and Stability of Pure Element Hollow Nanospheres and Nanotubes; Effect of Substrate Temperature on the Different Diffuseness of Subsequent Interfaces in Binary Multilayers Modeling of Diffusion Saturation of (+) Titanium Alloys by Nitrogen in the Rarefied Medium Suppression Criterion of the Phase Growth Based on Extremal Principles of Nonequilibrium Thermodynamics; Model of Lateral Growth Stage during Reactive Phase Formation; Coupling of Electromigration and Non-Equilibrium Vacancies in Reactive Phase Growth; Section 2 - Driven Systems; Mechano-Chemistry; Interdiffusion in Solid Solutions; Models of Mutual Solubility Increasing under the Pulse Loading; Cluster Dynamics Simulation of

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Sommario/riassunto

Diffusion-controlled processes still remain the most important and interesting phenomena in materials science. Among the problems which are currently to the fore, are the synergy of diffusion and morphological evolution, the initial stages of solid-state reactions, the analysis of nano- materials and related phenomena, thermo- and electromigration, and the reliability of solder joints and interconnects in microelectronic devices. A number of challenging problems still remain within the ""classical"" areas of nucleation, reactive- and interdiffusion, phase growth in multicomponent and binary s